

(19)
(12)

(KR)
(A)

(51) 。 Int. Cl. ⁷
G02F 1/1335

(11)
(43)

2002 - 0059956
2002 07 16

(21) 10 - 2001 - 0001138
(22) 2001 01 09

(71)

3 416

(72)

4 5 201

(74)

:

(54)

가

2f

1a 1d

2a 2f 1

,

3a 3e 2

,

4a 4f 3

,

5a 5f 4

,

6a 6b 가 가 20msec

,

,

7a 5 ,

7b 5 ,

7c 7a 7b ,

8a 6 ,

8b 6 ,

8c 8a 8b .

(color filter)

가

가

1a 1d

1a (photolithography) (10) (20) (21) (22)

1b 가 가 (30) (" ") 3

1c (30) ITO(indium tin oxide) (40)

TN(twisted nematic) 3 , 1

A(patterned vertically aligned) ") (40) (41) (" PV 1d

(41) (30)가 1 가 (30)가 가 가

(41) (40) , (40) PV

A 가

1 , 가 ,

2

2 가 1

가 ,

가 , 1

1

1 가 2 1

2 가

2a 2f 1

0) 2a (30) 가 1 3 (10) 3 (30) (30) (10) (30)

2b (40) (30) ITO IZO(indium zinc oxide)

2c (20) (40) (21) (22)

2d , BCB 가 가 (20) BCB (50) (50) (50)

2e (50) (ashing) (50) 150 / 가 (20) (50) 1.5 μ m 가 100 (margin) 5~50%

2f (20) (50) (20)

3
1 , PVA TN
2

3a 3e 2

2

, 3a (30) 가 1 3 (10) 3 (30) (10)

, 3b 1 (41) (30) ITO IZO(indium zinc oxide)

, 3c 1 (41) (60)

, 3d (60) (60) (60)

2 1

(60)가 가 2 (42) 3e

4a 4f 3

0) 4a (30) (10) 3 (30) (3) 5~15
) 가 8 μ m (10)

, 4b (40) (30) ITO IZO(indium zinc oxide)

, 4c (20) (40) (21) (22)

, 4d (2) 가 (1) (20) (70) (70) (1)
, 0.5 3.5 μ m 가

4d 가 (),
 가 ().
 (70) (

70)

4e (70) (70)
 (20)

4f (20) (70) (20)

3 3

5a 5f 4

5a (10) 3 (3
 0) (30) (30) () 5~15
)
 μm 가 $8\mu\text{m}$ (10)

5b (30) (21) (22)
 (20)

5c (20) BCB (50) (50)
 , BCB 가 BCB (50)
 가 , 0.5 $3.5\mu\text{m}$ 가

5d (50) (ashing) (50)
 (20) (margin)
 5~50%

5e (20) (50) (20)

5f (30) (50) ITO IZO(indium zinc oxide)
 (40)

4 (20)

3 TN
 1

6a 6b
 , 가 가 20msec

6a 6b
 가 PVA

7a 5
 7a (20) (20)
 (23)
 (24, 25)가 (24, 25) (24) 가
 (25) (20) 4

7b 5
 (100) (101) 가 (102) 가

7c 7a 7b
 (100) (101, 102) (20) (101,
 102) 가 , (20) 8 가 8 4 (101,
 가 , 4 가 ?? 가 . 4 4 2
 , 2 , 가
 4 2 , 2
 4
 가

8a 6
 (20) (23)
 (25)가 (20)
 3 , 3 (25) 2 가
 가

8b 6
 (100) 가 , 1
 (101)가 , 가 (102)가 , 1
 (100) 1 (101) , (102)
 3 . 3 가 2 2 2 (102)
 가 2

8c	8a	8b	.
		(20)	(101, 102)
	7a	7c	6

(57)

1.

,

가

,

1

,

2.

1

,

,

3.

1

,

,

4.

2

3

,

5.

1

,

6.

5 ,

2

7.

1 ,

1

2

8.

,

가

,

,

9.

8 ,

,

,

10.

가

,

1

,

1

,

,

11.

10 ,

12.

10 ,

13.

10 ,

14.

10 ,

2

15.

가 ,

1 ,

1 ,

16.

15 ,

2

17.

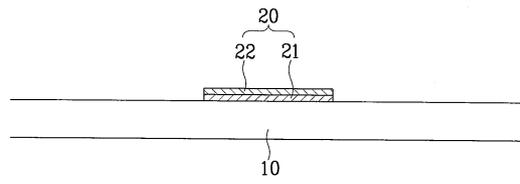
가 ,

,

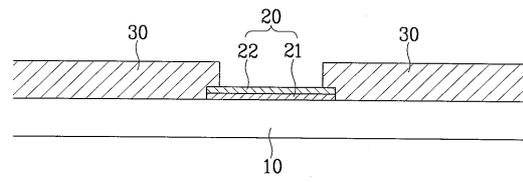
,

,

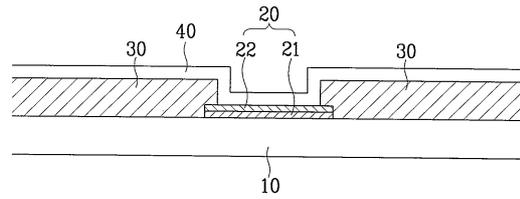
1a



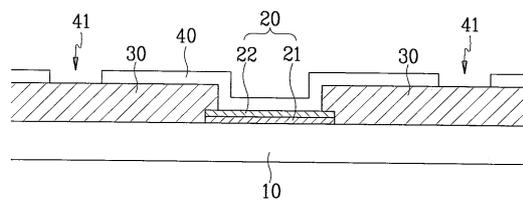
1b



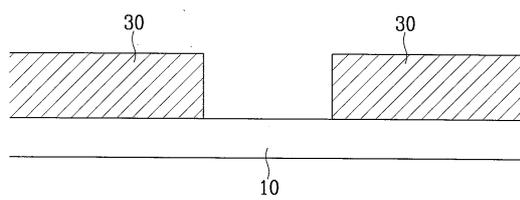
1c



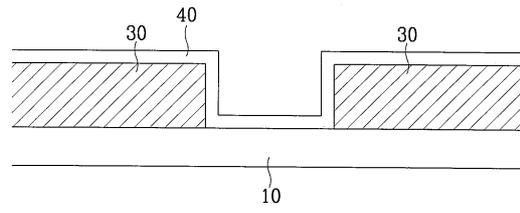
1d



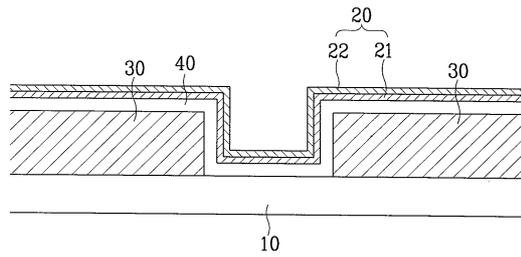
2a



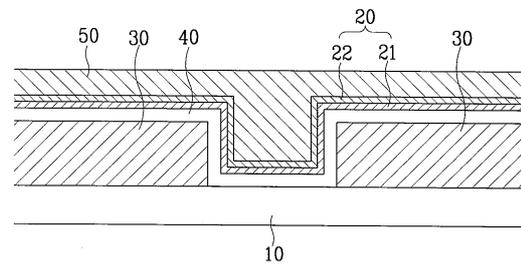
2b



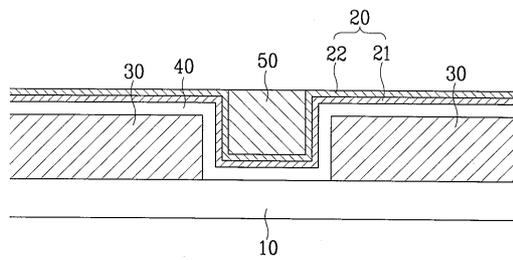
2c



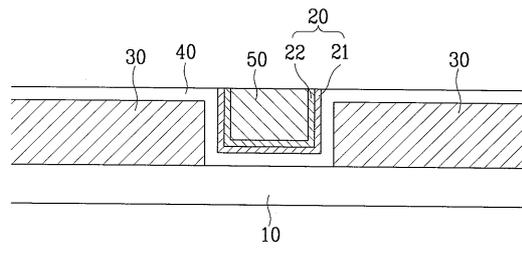
2d



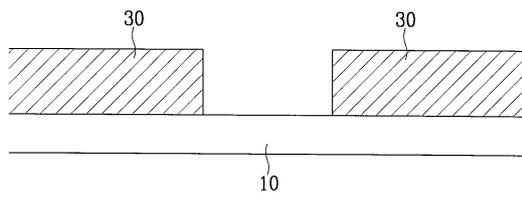
2e



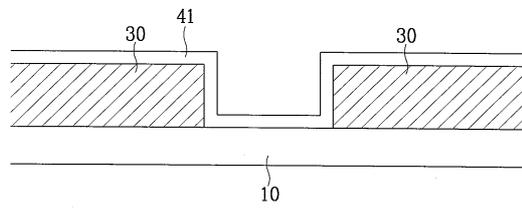
2f



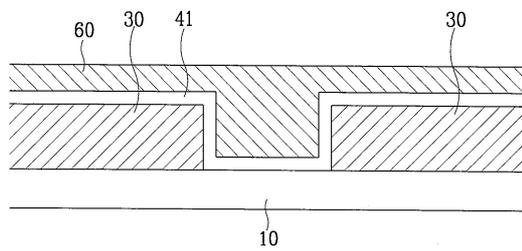
3a



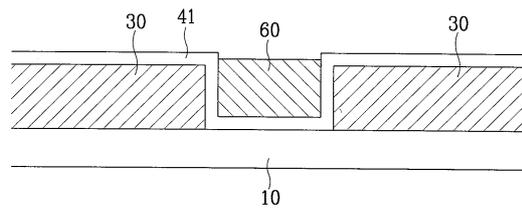
3b



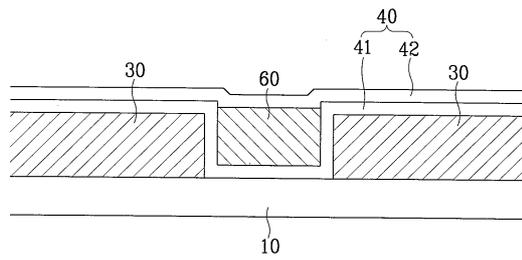
3c



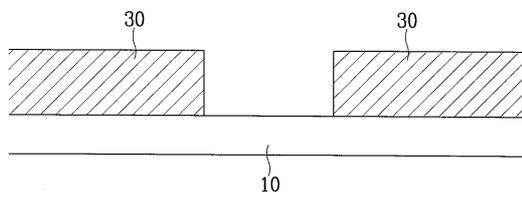
3d



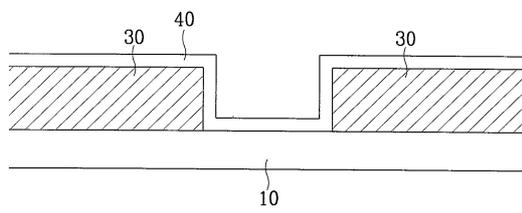
3e



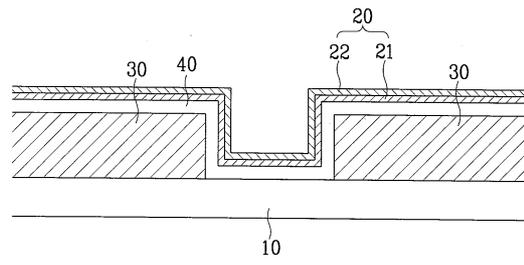
4a



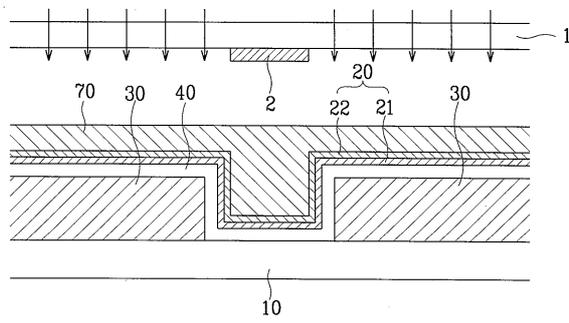
4b



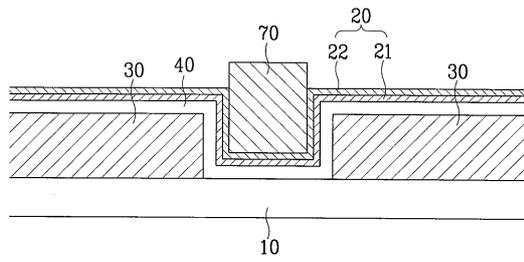
4c



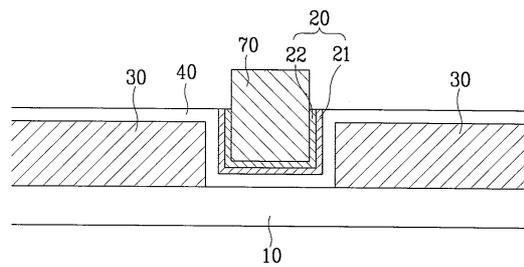
4d



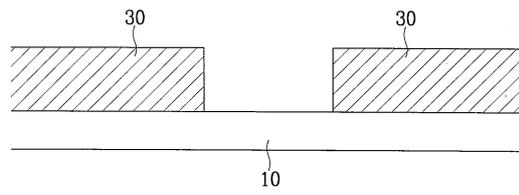
4e



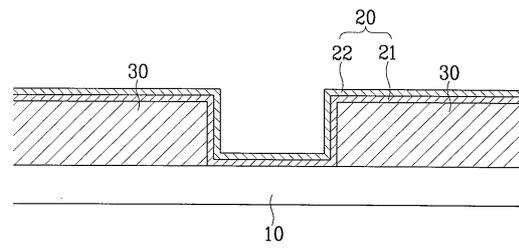
4f



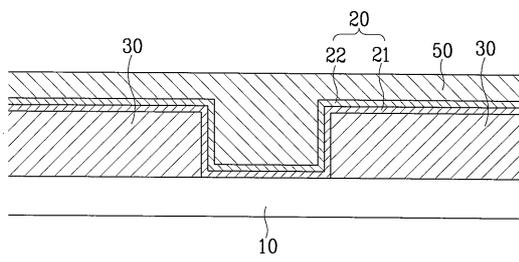
5a



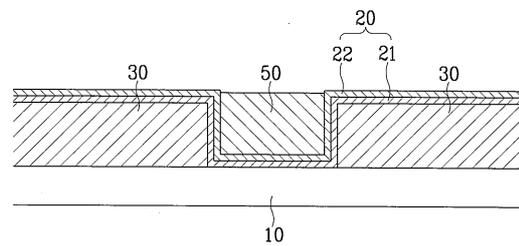
5b



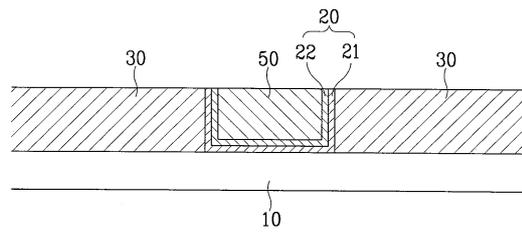
5c



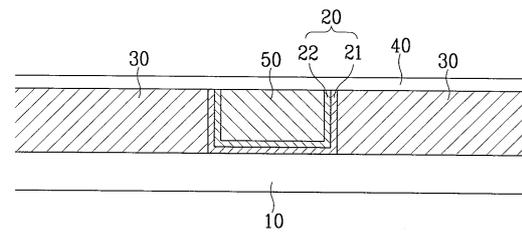
5d



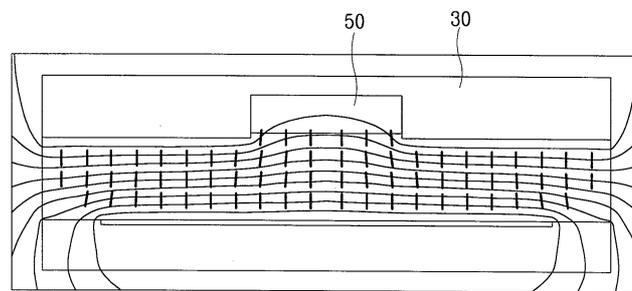
5e



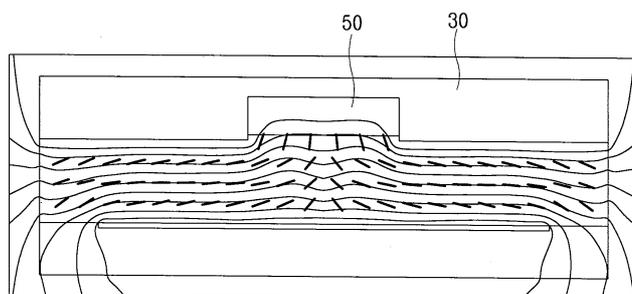
5f



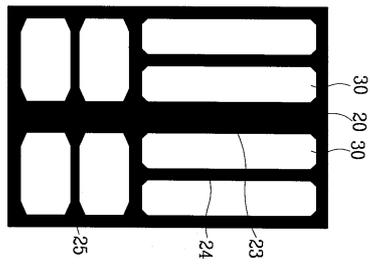
6a



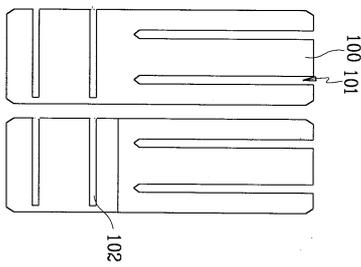
6b



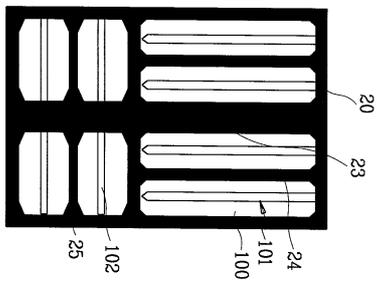
7a



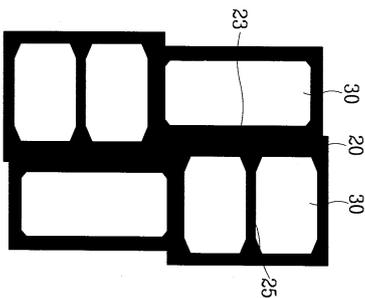
7b



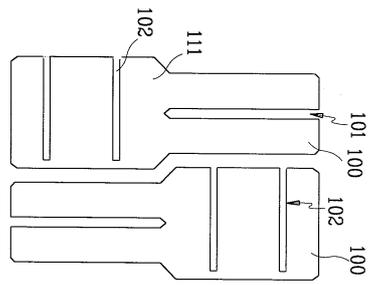
7c



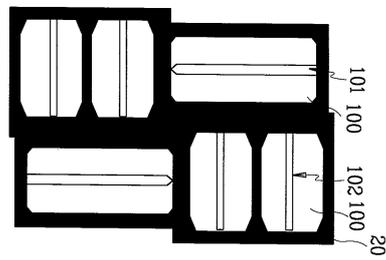
8a



8b



8c



专利名称(译)	用于液晶显示装置的基板及其制造方法		
公开(公告)号	KR1020020059956A	公开(公告)日	2002-07-16
申请号	KR1020010001138	申请日	2001-01-09
[标]申请(专利权)人(译)	三星电子株式会社		
申请(专利权)人(译)	三星电子有限公司		
当前申请(专利权)人(译)	三星电子有限公司		
[标]发明人	SONG JANGKUN 송장근		
发明人	송장근		
IPC分类号	G02F1/1333 G02B5/20 G02F1/1335 G03F7/40		
CPC分类号	G02F2001/133519 G02F1/133512 G02F2201/40 G02F1/133516 G02B5/201 Y10T428/10 Y10T428/2457 Y10T428/24612 Y10T428/24835 Y10T428/24876 Y10T428/24901		
代理人(译)	KIM, WON GUN 您是我的专利和法律公司		
其他公开文献	KR100686239B1		
外部链接	Espacenet		

摘要(译)

形成在透明基板上具有凹槽的滤色器。透明导电层沉积在滤色器上并形成公共电极。通过该系列在公共电极上沉积铬和氧化铬，并形成黑色矩阵。有机层形成在黑色矩阵上。灰化有机层，除去沟槽部分之外的剩余部分的有机层，并暴露黑色矩阵。暴露的黑色矩阵被蚀刻并移除。这样，简化了滤光器阵列面板的下侧和制造工艺。滤色片，黑色矩阵，有机层，灰化。

